

ABSTRACT OF THE DISCLOSURE

MARK POSITION DETERMINATION METHOD, LITHOGRAPHY METHOD,
METHOD OF MANUFACTURING ARTICLE, PROGRAM, AND
LITHOGRAPHY APPARATUS

A method of determining a mark position, includes determining, based on a position of a mark image on an image acquired by using a scope that captures an image of a mark, a temporary position of the mark image, determining a correction amount for correcting the temporary position based on a distortion map indicating a two-dimensional distribution of distortion amounts of the scope, and the mark image, and determining a position of the mark by correcting the temporary position based on the correction amount.

(Figure 6B)